



### Plasma Sources for Thin Film Deposition and Etching, 1st Edition



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M.A. Lieberman and R.A. Gottscho, Design of High-Density Plasma Sources for Materials Processing. O.A. Popov, Electron Cyclotron Resonance Plasma Sources and Their Use in Plasma-Assisted Chemical Vapor Deposition of Thin Films. S.L. Rohde, Unbalanced Magnetron Sputtering. C. Steinbruechel, The Formation of Particles in Thin-Film Processing Plasmas. References. Author Index. Subject Index.

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